## $NF_3$



Properties: Colorless, odorless, stable liquefied gas at room temperature and atmospheric pressure. The chemical property is relatively inert, but will interact violently with hydrogen. Decomposes into nitrogen difluoride and fluorine gas at about 350°C.

Uses: Dry etching in the electronics industry, wafer surface cleaning, and process etching chamber cleaning; Important special gas in photovoltaic/display/semiconductor manufacturing.

## · Identifier

## · Physical and chemical properties

Chemical Formula	NF <sub>3</sub>	Molecular weight	71 g/mol	Flash point	/	Reactivity	Non-flammable and non-explosive
CAS No.	7783-54-2	Appearance	colorless gas	Melting point	-207°C	Solubility	soluble in water
EINECS No.	232-007-1	Density	1.885 g/cm <sup>3</sup>	Boiling point	<b>-129</b> ℃	Storage	Shady and cool, well-ventilated

## ·Impurities

Impurities	Unit	Specification	Impurities	Unit	Specification
CF4	ppmv	≤30	N <sub>2</sub> O	ppmv	≤1
N <sub>2</sub>	ppmv	≤2	SF <sub>6</sub>	ppmv	≤1
O <sub>2</sub>	ppmv	≤2	H <sub>2</sub> O	ppmv	≤1
CO	ppmv	≤1	HF	ppmv	≤1
CO <sub>2</sub>	ppmv	≤1			



High Purity Materials Production Plant: No.16, Chuangxing Third Road, Qingyuan, Guangdong China 511517

Tel: 0763-3993123 Fax: (86) 020 - 83511907 Website: www.vitalchem.com

E-mail: semi\_sales@vitalchem.com

